

V2019  
VAKUUM & PLASMA

EFDS 



Die V im  
Zentrum!

8./10. OKTOBER 2019

INTERNAT. CONGRESS CENTER DRESDEN

Workshop

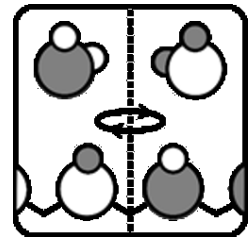
## Atomic Layer Deposition ALD

Wednesday, 09.10.2019, 13:30 – 17:30

Thursday, 10.10.2019, 09:00 – 12:30

Atomic Layer Deposition (ALD) is used to deposit ultraconformal thin films with sub-nm film thickness control. The method is unique in the sense that it employs sequential self-limiting surface reactions for growth in the monolayer thickness regime.

During this workshop specially ALD for optical and medical applications will be addressed beside others.



Scheme Atomic  
Layer Deposition

### Organizer:

- Fraunhofer-Institut für Keramische Technologien und Systeme IKTS, Dresden
- Europäische Forschungsgesellschaft Dünne Schichten e.V. (EFDS), Dresden

### Program Committee:

- Dr. Jonas Sundqvist, Fraunhofer-Institut für Keramische Technologien und Systeme IKTS, Dresden, Germany

### Workshop-Sponsors:



Picosun Oy  
[www.picosun.com](http://www.picosun.com)



plasway Technologies GmbH  
[www.plasway-technologies.de](http://www.plasway-technologies.de)

Program, Wednesday, 09.10.2019

### Lecture

Wednesday, October 9, 2019, 13:30 – 15:00

“45 years of ALD”

**Dr. Tuomo Suntola, Picosun Oy, Espoo Finland**  
Millenium Technology Prize 2018

“Current and Emerging ALD Processes, Precursors and Applications in High Volume Production”

**Dr. Jonas Sundqvist**  
Fraunhofer IKTS, Dresden, Germany

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## Workshop

16:00 – 16:30 | WS5 – V01

“TBA”

Adriana Szeghalmi, Fraunhofer-Institut für Angewandte Optik und Feinmechanik IOF, Jena, Germany

16:30 – 17:00 | WS5 – V02

**"Multi-layer Stacked ALD Coating for Hermetic Encapsulation of Implantable Biomedical Micro-devices"**

Christoph Hossbach, Picosun group, Espoo, Finland

17:00 – 17:30 | WS5 – V03

**"Fast plasma ALD employing de Laval Nozzles for high velocity precursor injection"**

Abhishekkumar Thakur, Plasway-Technologies GmbH, Dresden, Germany

## Program, Thursday, 10.10.2019

9:00 – 9:30 | WS5 – V04

**„Advances in quantitative characterization of thin films with help of AFM-based methods“**

Malgorzata Kopycinska-Müller, Fraunhofer-Institut für Keramische Technologien und Systeme IKTS, Dresden, Germany

9:30 – 10:00 | WS5 – V05

**„In situ metrology for Atomic Layer Deposition processes“**

Martin Knaut, Technische Universität Dresden, IHM, Dresden, Germany

10:00 – 10:30 | WS5 – V06

**„Conformality in Atomic Layer Deposition“**

Véronique Cremers, Plasma Electronic GmbH, Neuenburg, Germany

*10:30 – 11:00 Coffee Break in the Exhibition*

11:00 – 11:30 | WS5 – V07

**„Oxides for Electronics“**

Mari Napari, Department of Materials Science and Metallurgy, University of Cambridge, Cambridge, UK

11:30 – 12:00 | WS5 – V08

**"Atomic Layer Deposition of Indium Nitride using Hexacoordinated In–N Bonded Precursors and NH<sub>3</sub> Plasma"**

Nathan O’Brian, Linköping University, Linköping, Sweden

12:00 – 12:30 | WS5 – V09

“TBA”

Wenke Weinreich, Fraunhofer-Institut für Photonische Mikrosysteme IPMS CNT, Dresden, Germany